

## Referências Bibliográficas

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## A

### **Lista de Artigos Publicados no Doutorado**

#### **A.1**

##### **Artigos Relacionados a esta Tese**

1. Prioli, R.; Jacobsohn, L.G.; da Costa, M.E.H.M. e Freire, F.L.  
Nanotribological properties of amorphous carbon-fluorine films  
TRIBOLOGY LETTERS, 2003 , 15 , 177-180
2. Jacobsohn, L.G.; da Costa, M.E.H.M.; Trava-Airoldi, V. e Freire  
F. L. Hard amorphous carbon-fluorine films deposited by PECVD using  
 $C_2H_2 - CF_4$  gas mixtures as precursor atmospheres  
DIAMOND AND RELATED MATERIALS, 2003 , 12 , 2037-2041
3. da Costa, M.E.H.M; Baumvol, I.J.R; Radke, C.; Jacobsohn, L.G.; Zamora,  
R.R.M. e Freire, F.L.  
Effects of thermal annealing on the structural, mechanical and tribological  
properties of hard fluorinated carbon films deposited by plasma enhanced  
chemical vapor deposition  
JOURNAL OF VACUUM SCIENCE & TECHNOLOGY A: VACUUM, SUR-  
FACES, AND FILMS  
2004, 22 (6), 2321-2328

#### **A.2**

##### **Outros Artigos publicados**

1. Jacobsohn, L.G.; Capote, G.; da Costa, M.E.H.M.; Franceschini, D.F. e  
Freire, F.L.  
Nanoporosity in plasma deposited amorphous carbon films investigated by  
small-angle X-ray scattering  
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2. Ayala, P.; da Costa, M.E.H.M.; Prioli, R. e Freire, F.L.  
Nano- and micro-scale wear of fluorinated carbon films  
SURFACE & COATINGS TECHNOLOGY, 2004 , 182 , 335-341
3. Sanchez, C.M.T.; da Costa, M.E.H.M.; Zamora, R.R.M.; Prioli, R. e Freire, F.L.  
Nitrogen incorporation into hard fluorinated carbon films: nanoscale friction and structural modifications  
DIAMOND AND RELATED MATERIALS, 2004 , 13 , 1366-1370
4. Maia da Costa, M.E.H.M.; Sanchez, C.M.T.; Jacobsohn, L.G. e Freire, F.L.  
Structural, mechanical, and nanoscale tribological properties of nitrogen-incorporated fluorine-carbon films  
Aceito para publicação na Thin Solid Films